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	Application No.	Applicant(s)
	Application No.	
Notice of Allowability	10/656,848	LEUNG ET AL.
Notice of Anowability	Examiner	Art offic
	Rakesh K. Dhingra	1763
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication IGHTS. This application is subject	pplication. If not included on will be mailed in due course. THIS
1. X This communication is responsive to Applicant's remarks of	on 2 <sup>nd</sup> Non-final office action dt. 7/2	<u>1/06.</u> .
2. ⊠ The allowed claim(s) is/are <u>1-12</u> .		
3. ☐ Acknowledgment is made of a claim for foreign priority ur  a) ☐ All b) ☐ Some* c) ☐ None of the:		
1. Certified copies of the priority documents have		
2. Certified copies of the priority documents have		
3. Copies of the certified copies of the priority do	cuments have been received in this	s national stage application from the
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:	•	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply MENT of this application.	y complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EXAMINE es reason(s) why the oath or declar	R'S AMENDMENT or NOTICE OF ration is deficient.
5. CORRECTED DRAWINGS ( as "replacement sheets") mus	st be submitted.	
(a) I including changes required by the Notice of Draftspers	son's Patent Drawing Review ( PTC	0-948) attached
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner' Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	l.84(c)) should be written on the draw the header according to 37 CFR 1.121	vings in the front (not the back) of 1(d).
<ol> <li>DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT</li> </ol>	sit of BIOLOGICAL MATERIAL FOR THE DEPOSIT OF BIOLOGIC	must be submitted. Note the CAL MATERIAL.
•		
•		
Attachment(s)	5. Notice of Informal	Patent Application
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Dotice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>	6. Interview Summar	• •
	Paper No./Mail D	ate .
3. Information Disclosure Statements (PTO/SB/08),	7. 🛛 Examiner's Amend	dment/Comment
Paper No./Mail Date  4.  Examiner's Comment Regarding Requirement for Deposit	8. X Examiner's Statement of Reasons for Allowance	
of Biological Material	9. 🔲 Other	Λ
		Rakesh Dhingra

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Thomas S. Hahn on 9/26/06.

## In the Claims

The application has been amended as follows:

## Claim amendments

1. (Presently amended) A plasma ion source for producing negative ions, comprising:

a source chamber;

an RF antenna mounted external to the chamber;

an RF power source coupled to the RF antenna for generating a plasma containing positive ions in a gas in the source chamber;

a converter mounted in the source chamber and negatively biased with respect to the source chamber and plasma, which is a non-cesium containing plasma the converter being made of a non-cesium containing material and including a converter surface shaped and positioned in the source chamber so the positive ions impact the converter surface and by sputtering surface ionization produce negative ions substantially directed to be moved on or parallel to a longitudinal axis of the source chamber towards the an extraction aperture.

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## Allowable Subject Matter

The following is an examiner's statement of reasons for allowance:

Claim 1- Prior art (US Patent No. 4,602,161, Whealton et al) does not teach claim limitation interalia, "which is a non-cesium containing plasma the converter being made of a non-cesium containing material and including a converter surface shaped and positioned in the source chamber so the positive ions impact the converter surface and by sputtering surface ionization produce negative ions substantially directed to be moved on or parallel to a longitudinal axis of the source chamber towards the an extraction aperture".

Claims 1-12 allowed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rakesh K. Dhingra whose telephone number is (571)-272-5959. The examiner can normally be reached on 8:30 -6:00 (Monday - Friday). If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571)-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Rakesh Dhingra

Parviz Hassanzadeh Supervisory Patent Examiner Art Unit 1763